

Docket No.: 0171-1079PUS1
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Hiroki YOSHIKAWA et al.

Application No.: 10/811,924

Confirmation No.: 003156

Filed: March 30, 2004

Art Unit: 1756

For: PHOTOMASK BLANK, PHOTOMASK, AND
METHOD OF MANUFACTURE

Examiner: S. D. Rosasco

AMENDMENT IN RESPONSE TO NON-FINAL OFFICE ACTION

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

INTRODUCTORY COMMENTS

In response to the Office Action dated October 20, 2006, please amend the above-identified U.S. patent application as follows:

Remarks/Arguments begin on page 2 of this paper.